

2026 Optica Laser Congress

11–15 October 2026

Radisson Blu Hotel Lietuva
Vilnius, Lithuania

Optica Laser Congress is presented
as an in-person event with on-demand content.
Eastern European Summer Time (EEST, UTC+01:00).

Agenda of Sessions — Sunday, 11 October

08:00–18:30	Registration, Lobby
17:00–18:30	Welcome Reception, Skybar

Monday, 12 October

Eastern European Summer Time (EEST, UTC +01:00)	Zeta 1	Epsilon	Zeta 2	Beta 1	Beta 2
	ASSL	EUVXRAY	HILAS	LAC	MICS
07:30–18:30	Registration, Lobby				
08:30–10:00	AM1A • UV and EUV Sources	EM1B • Components for High Energy and High Power Lasers and Commissioning	HM1C • Attosecond Dynamics & High-Harmonic Spectroscopy of Matter	LM1D • Free Space Communications and Space	MM1E • Mid-IR Fiber Lasers
10:00–17:30	Exhibit Hours, Lobby				
10:00–10:30	Coffee Break with Exhibitors, Lobby <i>Sponsored by American Elements, IPG Photonics, and OPTOMAN</i>				
10:30–12:30	JM2A • Joint Plenary Session I, Zeta 1				
12:30–14:00	Lunch Break (on your own)				
14:00–16:00	AM3A • Large Scale Facilities and Oscillator Synchronization	EM1B • Compact X-ray Sources	HM3C • XUV/ Soft X-ray High-Harmonic Sources & Characterization	LM3D • Lasers for Biomedical	MM3E • Mid-IR and THz Sources
16:00–16:30	Coffee Break with Exhibitors, Lobby <i>Sponsored by American Elements, IPG Photonics, and OPTOMAN</i>				
16:30–18:30	AM4A • Visible and NIR Sources		HM4C • Laser Front-End Technology: Diode Pumping, Beam Combining, Compression & Control	JM4D • Joint Special Session (EUVXRAY and LAC): Laser-driven EUV Source and Supporting Materials	MM4E • Optical Parametric Oscillators & Amplifiers
19:30–22:30	Altechna Facility Tour, Offsite Location				

Key to Conference Abbreviations

ASSL = Advanced Solid State Lasers Conference
EUVXRAY = Compact EUV & X-Ray Light Sources
HILAS = High-Intensity Lasers and High-Field Phenomena
LAC = Laser Applications Conference
MICS = Mid-Infrared Coherent Sources

Agenda of Sessions — Tuesday, 13 October

Eastern European Summer Time (EEST, UTC +01:00)	Zeta 1	Epsilon	Zeta 2	Beta 1	Beta 2
	ASSL	Joint	Joint	LAC	MICS
07:30-19:00	Registration, ASSL				
08:30-10:30	ATu1A • Advanced Solid-State Gain Media: Crystals and Ceramics	JTu1B • Joint: Laser-Driven Plasma Secondary Sources: X-ray, EUV & Relativistic Plasma Optics (EUVXRAY and HILAS)		LTu1C • ML/ AI for Process Development and Monitoring	MTu1D • Integrated Photonics
10:00-17:30	Exhibit Hours, Lobby				
10:30-11:00	Coffee Break with Exhibitors, Lobby <i>Sponsored by American Elements, IPG Photonics, and OPTOMAN</i>				
11:00-13:00	ATu2A • Beam-Combined Sources	JTu2B • Joint: Laser-Wakefield Acceleration & Compact Particle Accelerators (EUVXRAY and HILAS)		LTu2C • Laser-Beam Delivery and Beam Manipulation of High-Power Laser Beams	MTu2D • Novel Phasematching Techniques
13:00-14:30	Lunch Break On Your Own				
14:30-16:00	ATu3A • Waveguides, Thin Films, and Integrated Photonics	JTu3B • Joint: Advanced Laser Wakefield Accelerators and their Potential for FELs (EUVXRAY and HILAS)	HTu3C • High-Intensity Lasers and High-Field Phenomena (HILAS) Terahertz Generation & Strong-Field Light-Matter Interaction	LTu3D • Surface Modification and Micromachining	MTu3E • Spectroscopic Sources
16:00-17:30	JTU4A • Joint Poster Session I, Zeta Foyer				
16:00-16:30	Coffee Break with Exhibitors, Lobby <i>Sponsored by American Elements, IPG Photonics, and OPTOMAN</i>				
17:30-19:00	ATu5A • Mode-Locked Oscillators	JTU5B • Joint: X-ray Free-Electron Oscillators (EUVXRAY and HILAS)		LTu5C • Additive Manufacturing: macro-micro-nano I	

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Agenda of Sessions — Wednesday, 14 October

Eastern European Summer Time (EEST, UTC +01:00)	Zeta 1	Epsilon	Zeta 2	Beta 1	Beta 2
	ASSL	EUVXRAY	HILAS	LAC	LAC
08:00–18:30	Registration				
08:30–10:00	AW1A • 2 µm Sources	JW1B • Joint FEL Symposium: High Repetition Rate Attosecond and Seeded FELs (EUVXRAY and HILAS)		LW1D • Additive Manufacturing: Macro-micro-nano II	LW1E • Frontiers in Laser Applications I
10:00–17:30	Exhibit Hours, Lobby				
10:00–10:30	Coffee Break with Exhibitors, Lobby <i>Sponsored by American Elements, IPG Photonics, and OPTOMAN</i>				
10:30–12:30	JW2A • Joint Plenary Session II, Zeta 1				
12:30–14:00	Lunch Break On Your Own				
14:00–16:00	AW3A • High-Power Glass and Fiber Systems	EW2B • Compact EUV and X-ray Sources and Applications	HW3B • High-Power Laser Front-Ends: Seeding, OPCPA & Broadband Pulse Synthesis	LW3C • Laser Processing for Next Generation Electronic Devices	
16:00–17:30	JW4A • Joint Poster Session II, Zeta Foyer				
16:00–16:30	Coffee Break with Exhibitors, Lobby <i>Sponsored by American Elements, IPG Photonics, and OPTOMAN</i>				
19:00–21:30	EKSMA Optics Networking Reception and Tour, Offsite Location				

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Agenda of Sessions —Thursday, 15 October

Eastern European Summer Time (EEST, UTC +01:00)	Zeta 1	Epsilon	Zeta 2	Beta 1	Beta 2
	ASSL	EUVXRAY	HILAS	LAC	MICS
08:00–16:30	Registration, Lobby				
08:30–10:30	ATH1A • Materials for Q-switched and Mode-Locked Lasers and Frequency Comb Generation	ETH1B • Table-top Attosecond Sources and Science	HTH1C • Petawatt Facility Commissioning & High-Energy Diode-Pumped Lasers	LTH1D • Fusion Energy	MF1E • OPCPA Systems
10:30–11:00	Coffee Break				
11:00–13:00	ATH2A • Nonlinear Conversion and Compression	ETH2B • Laser Driven Particle and X-ray Sources for Industrial Applications	HTH2C • High-Power Laser Hardware: Amplifiers, Optics & AI-Driven Facilities	LTH2D • Global Security and Aerospace	
13:00–14:30	Lunch Break On Your Own				
14:30–16:30	ATH3A • Materials for Nonlinear Optics and Frequency Conversion	ETH3B • High Order Harmonic Sources and Beamlines	HTH3C • Ultrafast Pulse Compression & Nonlinear Pulse Shaping	LTH3D • Frontiers in Laser Applications II	
17:00–19:00	OPTOMAN Facility Tour, Offsite Location				

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